

Mark J Kushner

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210
papers

8,880
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50
h-index

84
g-index

236
ext. papers

9,994
ext. citations

2.9
avg, IF

6.58
L-index

#	Paper	IF	Citations
210	The 2012 Plasma Roadmap. <i>Journal Physics D: Applied Physics</i> , 2012 , 45, 253001	3	425
209	A model for the discharge kinetics and plasma chemistry during plasma enhanced chemical vapor deposition of amorphous silicon. <i>Journal of Applied Physics</i> , 1988 , 63, 2532-2551	2.5	412
208	A model for plasma modification of polypropylene using atmospheric pressure discharges. <i>Journal Physics D: Applied Physics</i> , 2003 , 36, 666-685	3	349
207	Hybrid modelling of low temperature plasmas for fundamental investigations and equipment design. <i>Journal Physics D: Applied Physics</i> , 2009 , 42, 194013	3	222
206	Numerical investigation of the kinetics and chemistry of rf glow discharge plasmas sustained in He, N ₂ , O ₂ , He/N ₂ /O ₂ , He/CF ₄ /O ₂ , and SiH ₄ /NH ₃ using a Monte Carlo-fluid hybrid model. <i>Journal of Applied Physics</i> , 1992 , 71, 1654-1673	2.5	215
205	O ₂ (Π) production in He/O ₂ mixtures in flowing low pressure plasmas. <i>Journal of Applied Physics</i> , 2004 , 96, 2451-2465	2.5	210
204	Argon metastable densities in radio frequency Ar, Ar/O ₂ and Ar/CF ₄ electrical discharges. <i>Journal of Applied Physics</i> , 1997 , 82, 2805-2813	2.5	168
203	Reaction chemistry and optimization of plasma remediation of NxOy from gas streams. <i>Journal of Applied Physics</i> , 1995 , 78, 2074-2085	2.5	167
202	Atmospheric pressure dielectric barrier discharges interacting with liquid covered tissue. <i>Journal Physics D: Applied Physics</i> , 2014 , 47, 165201	3	150
201	Atmospheric pressure plasma jets interacting with liquid covered tissue: touching and not-touching the liquid. <i>Journal Physics D: Applied Physics</i> , 2014 , 47, 475203	3	140
200	Plasma remediation of trichloroethylene in silent discharge plasmas. <i>Journal of Applied Physics</i> , 1993 , 74, 5378-5386	2.5	138
199	A Comparison of Corona-Treated and Flame-Treated Polypropylene Films. <i>Plasmas and Polymers</i> , 2003 , 8, 61-95		134
198	Helium atmospheric pressure plasma jets touching dielectric and metal surfaces. <i>Journal of Applied Physics</i> , 2015 , 118, 013301	2.5	125
197	Plasma atomic layer etching using conventional plasma equipment. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2009 , 27, 37-50	2.9	123
196	Modeling of microdischarge devices: Pyramidal structures. <i>Journal of Applied Physics</i> , 2004 , 95, 846-859	2.5	123
195	Investigations of surface reactions during C ₂ F ₆ plasma etching of SiO ₂ with equipment and feature scale models. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2001 , 19, 524-538	2.9	123
194	Two-dimensional hybrid model of inductively coupled plasma sources for etching. <i>Applied Physics Letters</i> , 1993 , 63, 605-607	3.4	123

193	Removal of SO ₂ from gas streams using a dielectric barrier discharge and combined plasma photolysis. <i>Journal of Applied Physics</i> , 1991 , 69, 4409-4417	2.5	121
192	A general memristor-based partial differential equation solver. <i>Nature Electronics</i> , 2018 , 1, 411-420	28.4	112
191	Formation of reactive oxygen and nitrogen species by repetitive negatively pulsed helium atmospheric pressure plasma jets propagating into humid air. <i>Plasma Sources Science and Technology</i> , 2015 , 24, 035026	3.5	100
190	Simulation of the gas-phase processes in remote-plasma-activated chemical-vapor deposition of silicon dielectrics using rare gas/bilane-ammonia mixtures. <i>Journal of Applied Physics</i> , 1992 , 71, 4173-4189	2.5	99
189	Air plasma treatment of liquid covered tissue: long timescale chemistry. <i>Journal Physics D: Applied Physics</i> , 2016 , 49, 425204	3	99
188	Properties of c-C ₄ F ₈ inductively coupled plasmas. II. Plasma chemistry and reaction mechanism for modeling of Ar/c-C ₄ F ₈ /O ₂ discharges. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2004 , 22, 511	2.9	96
187	The role of negative ions in the formation of particles in low-pressure plasmas. <i>Journal of Applied Physics</i> , 1993 , 74, 853-861	2.5	95
186	A three-dimensional model for inductively coupled plasma etching reactors: Azimuthal symmetry, coil properties, and comparison to experiments. <i>Journal of Applied Physics</i> , 1996 , 80, 1337-1344	2.5	90
185	Monte Carlo-fluid hybrid model of the accumulation of dust particles at sheath edges in radio-frequency discharges. <i>Applied Physics Letters</i> , 1991 , 59, 638-640	3.4	89
184	Plasma chemistry of He/O ₂ /SiH ₄ and He/N ₂ O/SiH ₄ mixtures for remote plasma-activated chemical-vapor deposition of silicon dioxide. <i>Journal of Applied Physics</i> , 1993 , 74, 6538-6553	2.5	86
183	Excitation mechanisms of the electron-beam-pumped atomic xenon (5d-6p) laser in Ar/Xe mixtures. <i>Journal of Applied Physics</i> , 1989 , 66, 5131-5145	2.5	86
182	Excitation mechanisms and gain modeling of the high-pressure atomic Ar laser in He/Ar mixtures. <i>Journal of Applied Physics</i> , 1994 , 75, 1883-1890	2.5	84
181	Structure of positive streamers inside gaseous bubbles immersed in liquids. <i>Journal Physics D: Applied Physics</i> , 2009 , 42, 132003	3	82
180	A model for particulate contaminated glow discharges. <i>Journal of Applied Physics</i> , 1991 , 69, 6952-6961	2.5	78
179	Predictions of ion energy distributions and radical fluxes in radio frequency biased inductively coupled plasma etching reactors. <i>Journal of Applied Physics</i> , 1996 , 79, 2275-2286	2.5	74
178	Integrated plasma equipment model for polysilicon etch profiles in an inductively coupled plasma reactor with subwafer and superwafer topography. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1997 , 15, 1913-1921	2.9	73
177	Electron collisions with atoms, ions, molecules, and surfaces: Fundamental science empowering advances in technology. <i>Proceedings of the National Academy of Sciences of the United States of America</i> , 2016 , 113, 7026-34	11.5	70
176	Propagation mechanisms of guided streamers in plasma jets: the influence of electronegativity of the surrounding gas. <i>Plasma Sources Science and Technology</i> , 2015 , 24, 035022	3.5	67

175	Observations of electric discharge streamer propagation and capillary oscillations on the surface of air bubbles in water. <i>Journal Physics D: Applied Physics</i> , 2011 , 44, 082001	3	64
174	Experimental and modeling analysis of fast ionization wave discharge propagation in a rectangular geometry. <i>Physics of Plasmas</i> , 2011 , 18, 083505	2.1	62
173	A semianalytic radio frequency sheath model integrated into a two-dimensional hybrid model for plasma processing reactors. <i>Journal of Applied Physics</i> , 1997 , 81, 569-577	2.5	62
172	Modeling of magnetically enhanced capacitively coupled plasma sources: Ar discharges. <i>Journal of Applied Physics</i> , 2003 , 94, 1436-1447	2.5	61
171	Dynamics of a coplanar-electrode plasma display panel. II. Cell optimization. <i>Journal of Applied Physics</i> , 1999 , 85, 3470-3476	2.5	60
170	Plasma abatement of perfluorocompounds in inductively coupled plasma reactors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2000 , 18, 213-231	2.9	59
169	Destruction mechanisms for formaldehyde in atmospheric pressure low temperature plasmas. <i>Journal of Applied Physics</i> , 1993 , 73, 51-55	2.5	58
168	Consequences of propene and propane on plasma remediation of NO _x . <i>Journal of Applied Physics</i> , 2000 , 88, 3739-3747	2.5	57
167	Ion activation energy delivered to wounds by atmospheric pressure dielectric-barrier discharges: sputtering of lipid-like surfaces. <i>Journal Physics D: Applied Physics</i> , 2012 , 45, 115203	3	55
166	Trench filling by ionized metal physical vapor deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2001 , 19, 2652-2663	2.9	55
165	Mechanisms for CF ₂ radical generation and loss on surfaces in fluorocarbon plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2000 , 18, 2661-2668	2.9	55
164	Design issues in ionized metal physical vapor deposition of copper. <i>Journal of Applied Physics</i> , 1998 , 83, 35-43	2.5	54
163	The effect of radio frequency plasma processing reactor circuitry on plasma characteristics. <i>Journal of Applied Physics</i> , 1998 , 83, 5087-5094	2.5	54
162	Model for noncollisional heating in inductively coupled plasma processing sources. <i>Journal of Applied Physics</i> , 1997 , 81, 5966-5974	2.5	51
161	On the balance between silylene and silyl radicals in rf glow discharges in silane: The effect on deposition rates of a-Si:H. <i>Journal of Applied Physics</i> , 1987 , 62, 2803-2811	2.5	51
160	Streamer dynamics in gases containing dust particles. <i>Plasma Sources Science and Technology</i> , 2006 , 15, 591-602	3.5	50
159	Interaction between soot particles and NO _x during dielectric barrier discharge plasma remediation of simulated diesel exhaust. <i>Journal of Applied Physics</i> , 2000 , 88, 6060-6071	2.5	49
158	Helium atmospheric pressure plasma jets interacting with wet cells: delivery of electric fields. <i>Journal Physics D: Applied Physics</i> , 2016 , 49, 185201	3	49

157	Wave propagation and power deposition in magnetically enhanced inductively coupled and helicon plasma sources. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2001 , 19, 76-86 ^{2.9}	2.9	48
156	Integrated feature scale modeling of plasma processing of porous and solid SiO ₂ . I. Fluorocarbon etching. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2004 , 22, 1242-1259	2.9	46
155	Multiple microdischarge dynamics in dielectric barrier discharges. <i>Journal of Applied Physics</i> , 1998 , 84, 4153-4160	2.5	46
154	Computer simulation of materials processing plasma discharges. <i>Critical Reviews in Solid State and Materials Sciences</i> , 1989 , 16, 1-35	10.1	46
153	High energy electron fluxes in dc-augmented capacitively coupled plasmas. II. Effects on twisting in high aspect ratio etching of dielectrics. <i>Journal of Applied Physics</i> , 2010 , 107, 023309	2.5	45
152	Electron energy distributions in electron cyclotron resonance discharges for materials processing. <i>Journal of Applied Physics</i> , 1992 , 72, 33-42	2.5	45
151	Electron energy distributions and anomalous skin depth effects in high-plasma-density inductively coupled discharges. <i>Physical Review E</i> , 2002 , 66, 066411	2.4	44
150	Solving the spatially dependent Boltzmann equation for the electron-velocity distribution using flux corrected transport. <i>Journal of Applied Physics</i> , 1989 , 66, 5763-5774	2.5	44
149	Propagation of negative electrical discharges through 2-dimensional packed bed reactors. <i>Journal Physics D: Applied Physics</i> , 2017 , 50, 025203	3	43
148	450 mm dual frequency capacitively coupled plasma sources: Conventional, graded, and segmented electrodes. <i>Journal of Applied Physics</i> , 2010 , 108, 113306	2.5	43
147	Pulsed plasmas as a method to improve uniformity during materials processing. <i>Journal of Applied Physics</i> , 2004 , 96, 82-93	2.5	41
146	Mutual shielding of closely spaced dust particles in low pressure plasmas. <i>Journal of Applied Physics</i> , 1994 , 75, 3351-3357	2.5	39
145	Breakdown characteristics in nonplanar geometries and hollow cathode pseudospark switches. <i>Journal of Applied Physics</i> , 1992 , 71, 94-100	2.5	39
144	Plasma-induced flow instabilities in atmospheric pressure plasma jets. <i>Applied Physics Letters</i> , 2017 , 111, 114101	3.4	38
143	Two-dimensional modeling of long-term transients in inductively coupled plasmas using moderate computational parallelism. I. Ar pulsed plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2002 , 20, 313-324	2.9	38
142	Radially dependent solutions of Boltzmann equation in low-temperature plasmas using a modified two-term expansion. <i>Journal of Applied Physics</i> , 1993 , 73, 1080-1090	2.5	38
141	Chemical kinetics in an atmospheric pressure helium plasma containing humidity. <i>Physical Chemistry Chemical Physics</i> , 2018 , 20, 24263-24286	3.6	38
140	Atmospheric pressure plasma activation of water droplets. <i>Journal Physics D: Applied Physics</i> , 2019 , 52, 355207	3	36

139	Long-term effects of multiply pulsed dielectric barrier discharges in air on thin water layers over tissue: stationary and random streamers. <i>Journal Physics D: Applied Physics</i> , 2015 , 48, 494002	3	36
138	Seasoning of plasma etching reactors: Ion energy distributions to walls and real-time and run-to-run control strategies. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2008 , 26, 498-512	2.9	36
137	Continuous processing of polymers in repetitively pulsed atmospheric pressure discharges with moving surfaces and gas flow. <i>Journal Physics D: Applied Physics</i> , 2007 , 40, 6953-6968	3	36
136	Noncollisional heating and electron energy distributions in magnetically enhanced inductively coupled and helicon plasma sources. <i>Journal of Applied Physics</i> , 2001 , 90, 3699-3712	2.5	36
135	Two-dimensional modeling of long-term transients in inductively coupled plasmas using moderate computational parallelism. II. Ar/Cl ₂ pulsed plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2002 , 20, 325-334	2.9	36
134	Monte Carlo simulation of surface kinetics during plasma enhanced chemical vapor deposition of SiO ₂ using oxygen/tetraethoxysilane chemistry. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1993 , 11, 2562-2571	2.9	36
133	Ion composition of expanding microdischarges in dielectric barrier discharges. <i>Journal of Applied Physics</i> , 1998 , 83, 7522-7532	2.5	35
132	Consequences of asymmetric pumping in low pressure plasma processing reactors: A three-dimensional modeling study. <i>Journal of Applied Physics</i> , 1997 , 82, 5312-5320	2.5	34
131	Electron transport coefficients in dusty argon plasmas. <i>Applied Physics Letters</i> , 1989 , 55, 951-953	3.4	34
130	Molecular admixtures and impurities in atmospheric pressure plasma jets. <i>Journal of Applied Physics</i> , 2018 , 124, 153303	2.5	34
129	Atomic layer etching of 3D structures in silicon: Self-limiting and nonideal reactions. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 031306	2.9	33
128	Self-consistent three-dimensional model of dust particle transport and formation of Coulomb crystals in plasma processing reactors. <i>Journal of Applied Physics</i> , 2002 , 92, 6451-6460	2.5	33
127	Ion drag effects in inductively coupled plasmas for etching. <i>Applied Physics Letters</i> , 1996 , 68, 903-905	3.4	32
126	A phenomenological model for surface deposition kinetics during plasma and sputter deposition of amorphous hydrogenated silicon. <i>Journal of Applied Physics</i> , 1987 , 62, 4763-4772	2.5	32
125	Controlling VUV photon fluxes in low-pressure inductively coupled plasmas. <i>Plasma Sources Science and Technology</i> , 2015 , 24, 034017	3.5	31
124	Influence of modeling and simulation on the maturation of plasma technology: Feature evolution and reactor design. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2003 , 21, S152-S156	2.9	31
123	Role of neutral transport in aspect ratio dependent plasma etching of three-dimensional features. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 05C301	2.9	30
122	Plasma etching of high aspect ratio features in SiO ₂ using Ar/C ₄ F ₈ /O ₂ mixtures: A computational investigation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 031304 ^{2.9}	2.9	30

121	Control of electron energy distributions and plasma characteristics of dual frequency, pulsed capacitively coupled plasmas sustained in Ar and Ar/CF ₄ /O ₂ . <i>Plasma Sources Science and Technology</i> , 2012 , 21, 055028	3.5	30
120	Monte Carlo Simulation of the Electrodeposition of Copper. <i>Journal of the Electrochemical Society</i> , 2002 , 149, C396	3.9	30
119	Modeling of magnetically enhanced capacitively coupled plasma sources: Ar/C ₄ F ₈ /O ₂ discharges. <i>Journal of Applied Physics</i> , 2004 , 95, 834-845	2.5	29
118	The effects of He addition on the performance of the fission-fragment excited Ar/Xe atomic xenon laser. <i>Journal of Applied Physics</i> , 1991 , 69, 1843-1848	2.5	29
117	Monte Carlo-fluid model of chlorine atom production in Cl ₂ , HCl, and CCl ₄ radio-frequency discharges for plasma etching. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 1992 , 10, 2179		28
116	Transient behavior in quasi-atomic layer etching of silicon dioxide and silicon nitride in fluorocarbon plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 06B101	2.9	28
115	Controlling VUV photon fluxes in pulsed inductively coupled Ar/Cl ₂ plasmas and potential applications in plasma etching. <i>Plasma Sources Science and Technology</i> , 2017 , 26, 024005	3.5	27
114	Calculated cross sections for electron collisions with NF ₃ , NF ₂ and NF with applications to remote plasma sources. <i>Plasma Sources Science and Technology</i> , 2017 , 26, 065010	3.5	27
113	Simulation of the shielding of dust particles in low pressure glow discharges. <i>Applied Physics Letters</i> , 1993 , 62, 2197-2199	3.4	27
112	Electrode configurations in atmospheric pressure plasma jets: production of reactive species. <i>Plasma Sources Science and Technology</i> , 2018 , 27, 105020	3.5	27
111	Electron-beam controlled radio frequency discharges for plasma processing. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1996 , 14, 2094-2101	2.9	26
110	Investigation of feature orientation and consequences of ion tilting during plasma etching with a three-dimensional feature profile simulator. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 021303	2.9	25
109	Branching and path-deviation of positive streamers resulting from statistical photon transport. <i>Plasma Sources Science and Technology</i> , 2014 , 23, 065041	3.5	25
108	Fluorine Plasma Treatments of Polypropylene Films, 1 [Surface Characterization. <i>Plasma Processes and Polymers</i> , 2010 , 7, 107-122	3.4	25
107	Investigation of capillary nanosecond discharges in air at moderate pressure: comparison of experiments and 2D numerical modelling. <i>Journal Physics D: Applied Physics</i> , 2014 , 47, 365202	3	24
106	Fluorine Plasma Treatments of Poly(propylene) Films, 2 [Modeling Reaction Mechanisms and Scaling. <i>Plasma Processes and Polymers</i> , 2010 , 7, 123-150	3.4	23
105	Multi-scale simulation of functionalization of rough polymer surfaces using atmospheric pressure plasmas. <i>Journal Physics D: Applied Physics</i> , 2006 , 39, 1594-1598	3	23
104	A Monte Carlo simulation of radiation trapping in electrodeless gas discharge lamps. <i>Journal Physics D: Applied Physics</i> , 2004 , 37, 1780-1791	3	22

103	Translationally hot neutrals in etching discharges. <i>Journal of Applied Physics</i> , 1991 , 70, 1240-1251	2.5	22
102	Simulation of the switching performance of an optically triggered pseudo-spark thyatron. <i>Journal of Applied Physics</i> , 1989 , 66, 2325-2331	2.5	22
101	Plasma kinetics in a nanosecond pulsed filamentary discharge sustained in Ar+H ₂ O and H ₂ O. <i>Journal Physics D: Applied Physics</i> , 2019 , 52, 044003	3	22
100	High energy electron fluxes in dc-augmented capacitively coupled plasmas I. Fundamental characteristics. <i>Journal of Applied Physics</i> , 2010 , 107, 023308	2.5	21
99	Penetration of plasma into the wafer-focus ring gap in capacitively coupled plasmas. <i>Journal of Applied Physics</i> , 2007 , 101, 113307	2.5	21
98	Pulsed inductively coupled chlorine plasmas in the presence of a substrate bias. <i>Applied Physics Letters</i> , 2001 , 79, 2145-2147	3.4	21
97	A model for transport and agglomeration of particles in reactive ion etching plasma reactors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1996 , 14, 562-566	2.9	21
96	Shapes of agglomerates in plasma etching reactors. <i>Journal of Applied Physics</i> , 1997 , 81, 5960-5965	2.5	20
95	Regimes of particle trapping in inductively coupled plasma processing reactors. <i>Applied Physics Letters</i> , 1996 , 68, 3716-3718	3.4	20
94	Response times and energy partitioning in electron-beam-excited plasmas. <i>Journal of Applied Physics</i> , 1989 , 66, 2297-2306	2.5	20
93	Ionization wave propagation in an atmospheric pressure plasma multi-jet. <i>Plasma Sources Science and Technology</i> , 2019 , 28, 125009	3.5	19
92	Modeling of implantation and mixing damage during etching of SiO ₂ over Si in fluorocarbon plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2011 , 29, 051306	2.9	19
91	Microdischarges for use as microthrusters: modelling and scaling. <i>Journal Physics D: Applied Physics</i> , 2008 , 41, 105208	3	19
90	Synthesis of Silicon Nanoparticles in Nonthermal Capacitively-Coupled Flowing Plasmas: Processes and Transport. <i>Plasma Chemistry and Plasma Processing</i> , 2016 , 36, 941-972	3.6	19
89	Ion energy and angular distributions into the wafer-focus ring gap in capacitively coupled discharges. <i>Journal Physics D: Applied Physics</i> , 2008 , 41, 062004	3	18
88	Formation of XeI(B) in low pressure inductive radio frequency electric discharges sustained in mixtures of Xe and I ₂ . <i>Journal of Applied Physics</i> , 1996 , 80, 5593-5597	2.5	18
87	Atmospheric pressure plasma jets onto a reactive water layer over tissue: pulse repetition rate as a control mechanism. <i>Journal Physics D: Applied Physics</i> , 2019 , 52, 015201	3	18
86	Simulation of the formation of two-dimensional Coulomb liquids and solids in dusty plasmas. <i>Journal of Applied Physics</i> , 1997 , 82, 2106-2114	2.5	17

85	Comparison of two-dimensional and three-dimensional models for profile simulation of poly-Si etching of finite length trenches. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1998 , 16, 3274-3280	2.9	17
84	The effect of subwafer dielectrics on plasma properties in plasma etching reactors. <i>Journal of Applied Physics</i> , 1995 , 77, 3668-3673	2.5	17
83	Multi-beam-bulk model for electron transport during commutation in an optically triggered pseudospark thyratron. <i>Applied Physics Letters</i> , 1990 , 57, 1619-1621	3.4	17
82	Insights to scaling remote plasma sources sustained in NF ₃ mixtures. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 031302	2.9	16
81	Ionization wave propagation on a micro cavity plasma array. <i>Applied Physics Letters</i> , 2011 , 99, 141504	3.4	16
80	Integrated feature scale modeling of plasma processing of porous and solid SiO ₂ . II. Residual fluorocarbon polymer stripping and barrier layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2004 , 22, 1260-1274	2.9	16
79	Modeling of high power semiconductor switches operated in the nonlinear mode. <i>Journal of Applied Physics</i> , 1996 , 79, 2084-2090	2.5	16
78	Discharge instabilities initiated by nonuniform laser extraction in electron-beam sustained discharge KrF lasers. <i>Journal of Applied Physics</i> , 1987 , 62, 101-107	2.5	16
77	The consequences of air flow on the distribution of aqueous species during dielectric barrier discharge treatment of thin water layers. <i>Plasma Sources Science and Technology</i> , 2016 , 25, 055020	3.5	16
76	Space and phase resolved ion energy and angular distributions in single- and dual-frequency capacitively coupled plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2013 , 31, 061311	2.9	15
75	Angular anisotropy of electron energy distributions in inductively coupled plasmas. <i>Journal of Applied Physics</i> , 2003 , 94, 5522-5529	2.5	15
74	Short pulse electron beam excitation of the high-pressure atomic Ne laser. <i>Journal of Applied Physics</i> , 1993 , 73, 8059-8065	2.5	15
73	Three-dimensional measurements of plasma parameters in an inductively coupled plasma processing chamber. <i>Physics of Plasmas</i> , 2019 , 26, 103503	2.1	14
72	Highly selective Si ₃ N ₄ /SiO ₂ etching using an NF ₃ /N ₂ /O ₂ /H ₂ remote plasma. I. Plasma source and critical fluxes. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020 , 38, 023007-9	2.9	14
71	Time-resolved evolution of micro-discharges, surface ionization waves and plasma propagation in a two-dimensional packed bed reactor. <i>Plasma Sources Science and Technology</i> , 2018 , 27, 085002	3.5	14
70	A Monte-Carlo model of xenon resonance radiation transport in a plasma display panel cell: Transition from optically thick to thin regimes. <i>Journal of Applied Physics</i> , 2000 , 87, 2700-2707	2.5	14
69	Consequences of three-dimensional physical and electromagnetic structures on dust particle trapping in high plasma density material processing discharges. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1998 , 16, 2454-2462	2.9	14
68	The effect of CO ₂ on the plasma remediation of NxOy. <i>Applied Physics Letters</i> , 1996 , 68, 2064-2066	3.4	14

67	Monte Carlo hydrodynamic simulation of neutral radical transport in low pressure remote plasma activated chemical vapor deposition. <i>Applied Physics Letters</i> , 1993 , 62, 1594-1596	3.4	14
66	Fission fragment pumping of a neon plasma. <i>Journal of Applied Physics</i> , 1988 , 63, 1796-1798	2.5	14
65	Downstream etching of silicon nitride using continuous-wave and pulsed remote plasma sources sustained in Ar/NF ₃ /O ₂ mixtures. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 021305	2.9	13
64	Electron energy distributions in a magnetized inductively coupled plasma. <i>Physics of Plasmas</i> , 2014 , 21, 093512	2.1	13
63	Heavy-ion versus electron-beam excitation of an excimer laser. <i>Journal of Applied Physics</i> , 1988 , 64, 3799-3810	2.3	13
62	Plasma-driven solution electrolysis. <i>Journal of Applied Physics</i> , 2021 , 129, 200902	2.5	13
61	Numerical study of the influence of surface reaction probabilities on reactive species in an rf atmospheric pressure plasma containing humidity. <i>Plasma Physics and Controlled Fusion</i> , 2018 , 60, 014035	2	13
60	The role of thermal energy accommodation and atomic recombination probabilities in low pressure oxygen plasmas. <i>Plasma Physics and Controlled Fusion</i> , 2017 , 59, 024004	2	12
59	Controller design issues in the feedback control of radio frequency plasma processing reactors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1999 , 17, 704-712	2.9	12
58	Pulsed plasma-pulsed injection sources for remote plasma activated chemical vapor deposition. <i>Journal of Applied Physics</i> , 1993 , 73, 4098-4100	2.5	12
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